

Supporting Information

Engineering Pore Nanospaces through Introducing Aromatic Effect in UiO-66 for Efficient Light Hydrocarbons Separation

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S1. Materials and Instrumentation

All reagents and solvents were obtained from commercial sources and used without further purification. Powder X-ray diffraction (PXRD) were recorded ranging from 2 ° to 50 ° at room temperature on a RigakuSmartLab diffractometer (Bragg-Brentano geometry, Cu K α 1 radiation, λ = 1.54056 Å) at 40 kV and 15 mA. Thermogravimetric analysis (TGA) was performed on a NETZSCH TG209 system in nitrogen and under 1 atm of pressure at a heating rate of 10 °C min⁻¹. N₂ adsorption isotherms for pressures in the range of 0-1.0 bar were collected by a volumetric method using a quantachrome autosorb IQ3 gas adsorption analyzer. The samples were vacuumed at 100 °C for 12 h before the sorption examination. Gas adsorption isotherms were measured on a quantachrome Autosorb-iQ2-MP gas adsorption analyzer. The breakthrough curves were collected by a home-made instrument using a gas chromatography (FL-9790 plus) as detector.

S2. Powder X-Ray Diffraction

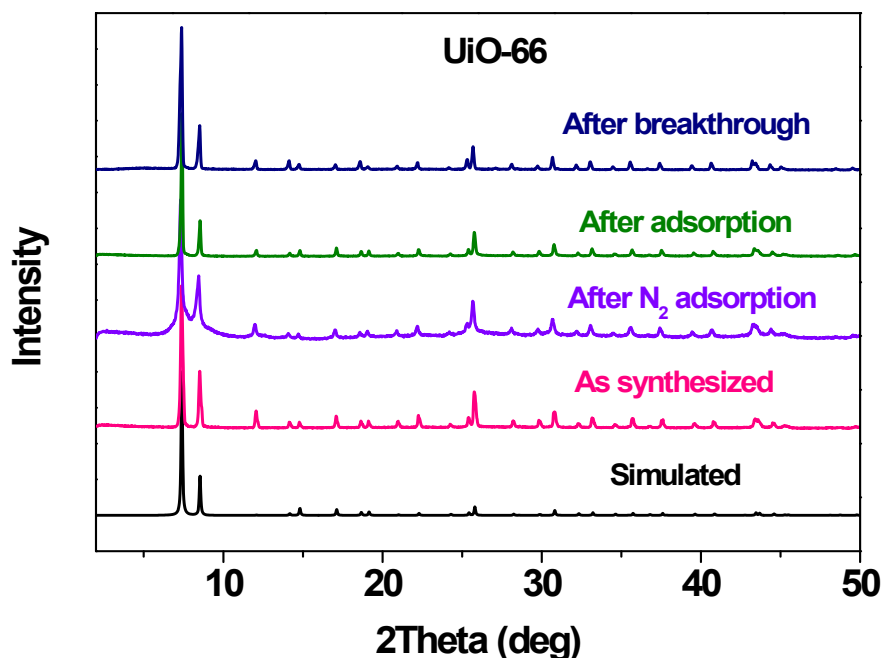


Figure S1. The simulated and experimental PXRD patterns of UiO-66.

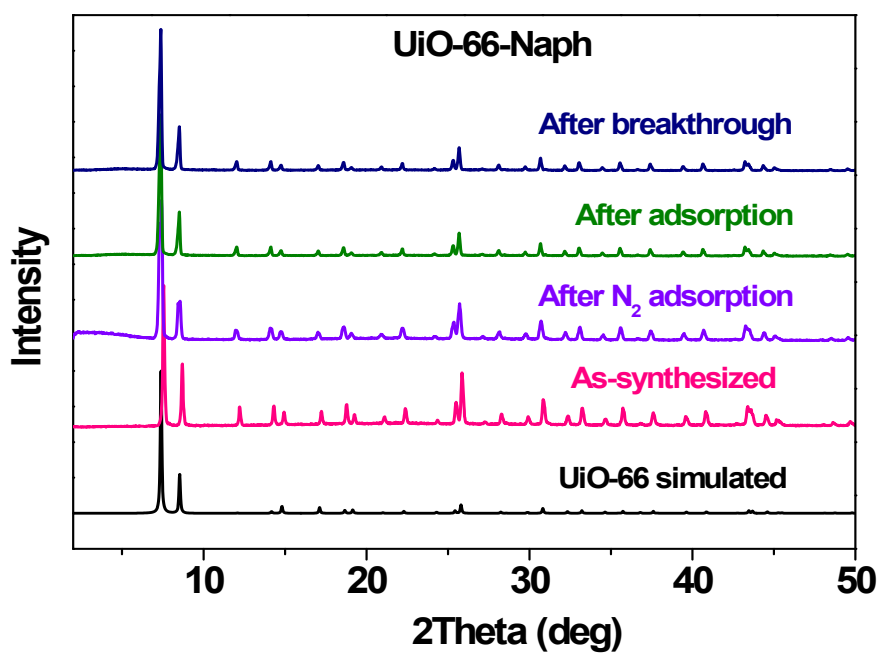


Figure S2. The simulated and experimental PXRD patterns of UiO-66-Naph.

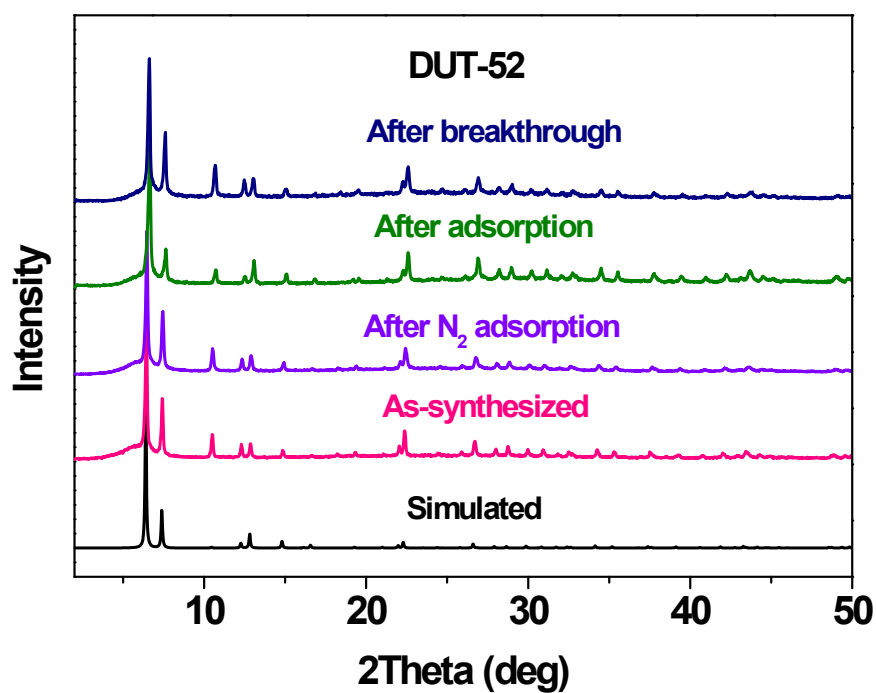


Figure S3. The simulated and experimental PXRD patterns of DUT-52.

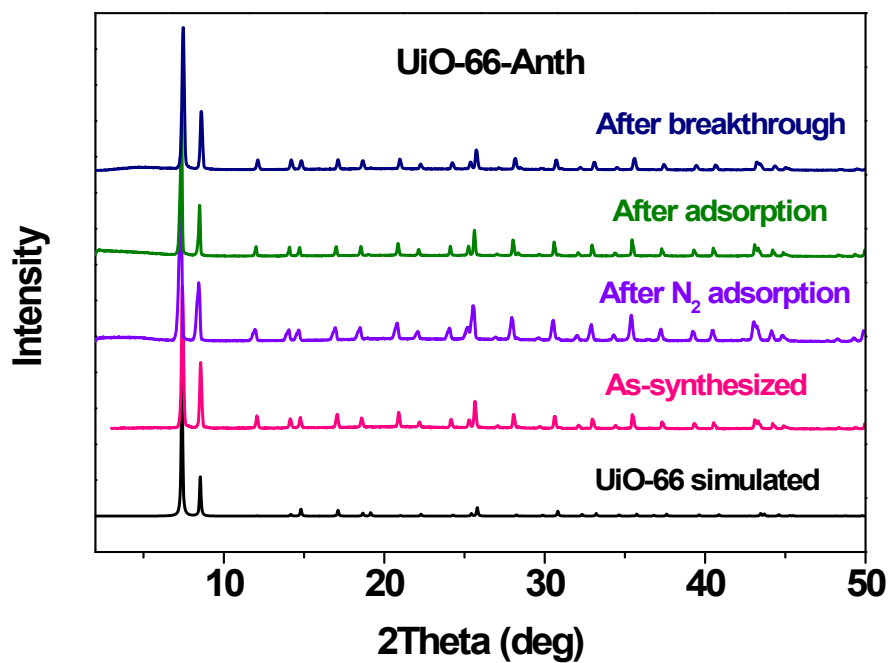


Figure S4. The simulated and experimental PXRD patterns of UiO-66-Anth.

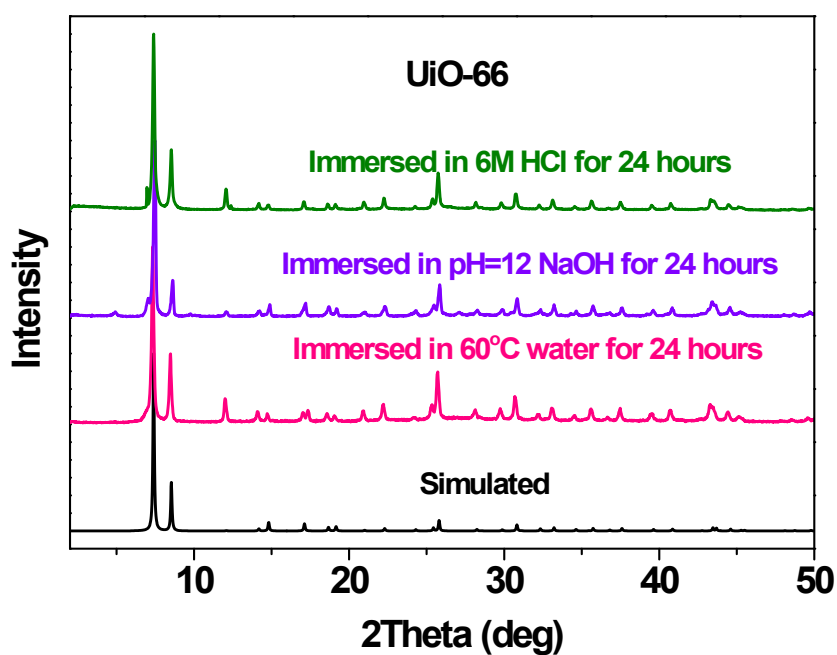


Figure S5. PXRD patterns of UiO-66 immersed in 6M HCl, pH = 12 NaOH and 60 °C H₂O for 24 h, respectively.

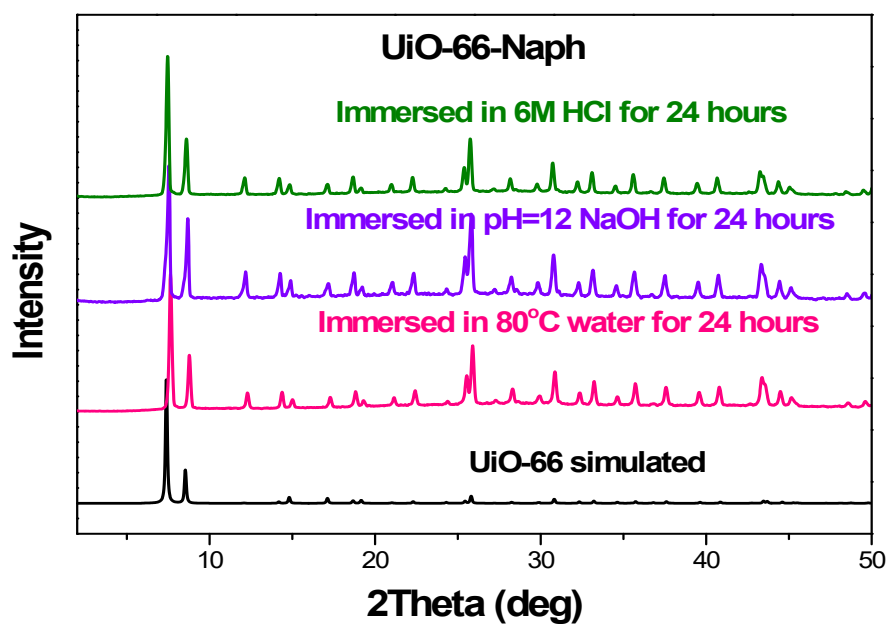


Figure S6. PXRD patterns of UiO-66-Naph immersed in 6M HCl, pH = 12 NaOH and 80 °C water for 24 h, respectively.

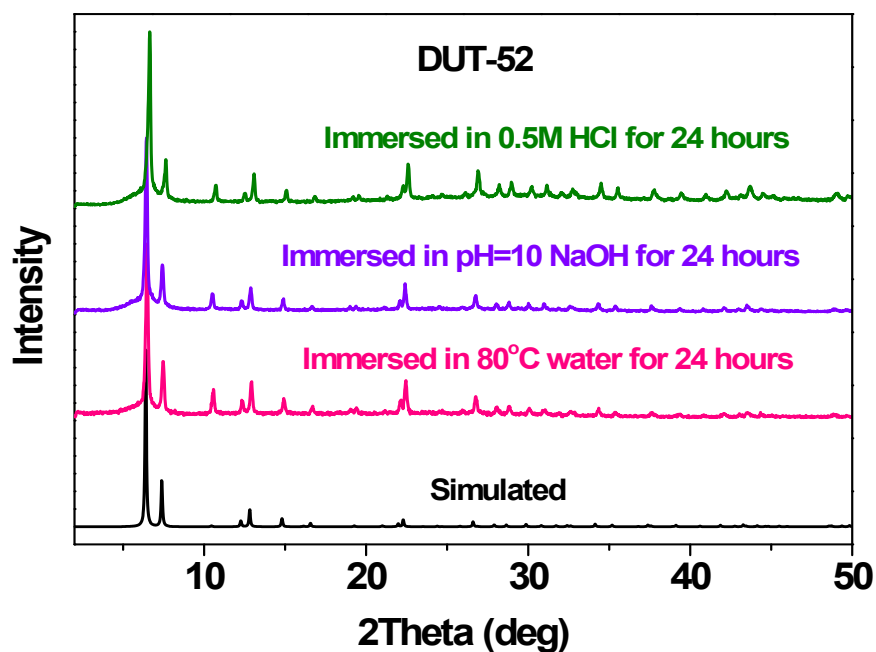


Figure S7. PXRD patterns of DUT-52 immersed in 0.5 M HCl, pH = 10 NaOH and 80 °C water for 24 h, respectively.

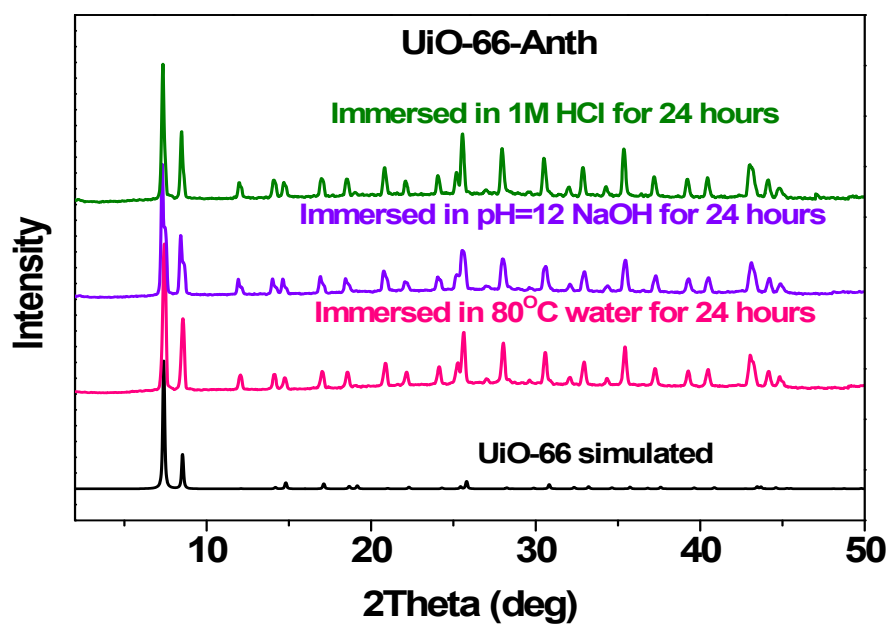


Figure S8. PXRD patterns of UiO-66-Anth immersed in 1M HCl, pH = 12 NaOH and 80 °C water for 24 h, respectively.

S3. Thermal Stability Analysis

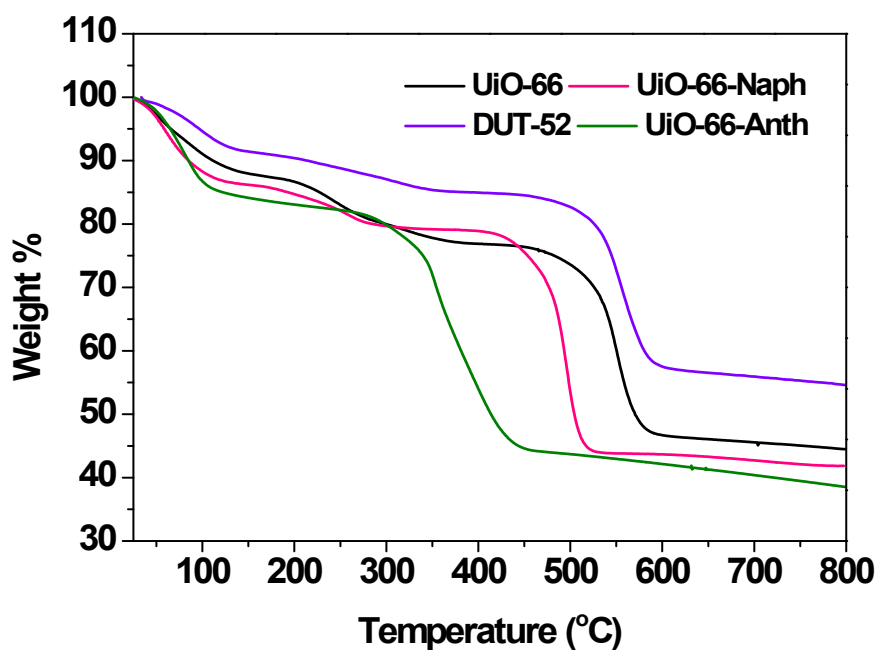


Figure S9. The thermogravimetric analyses of as-synthesized MOFs.

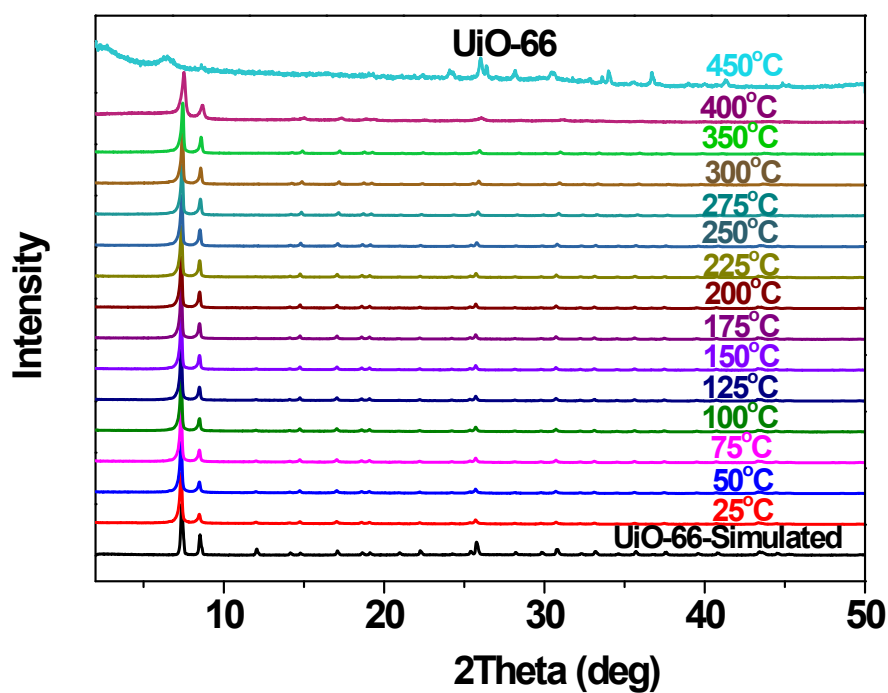


Figure S10. The variable-temperature PXRD patterns of UiO-66.

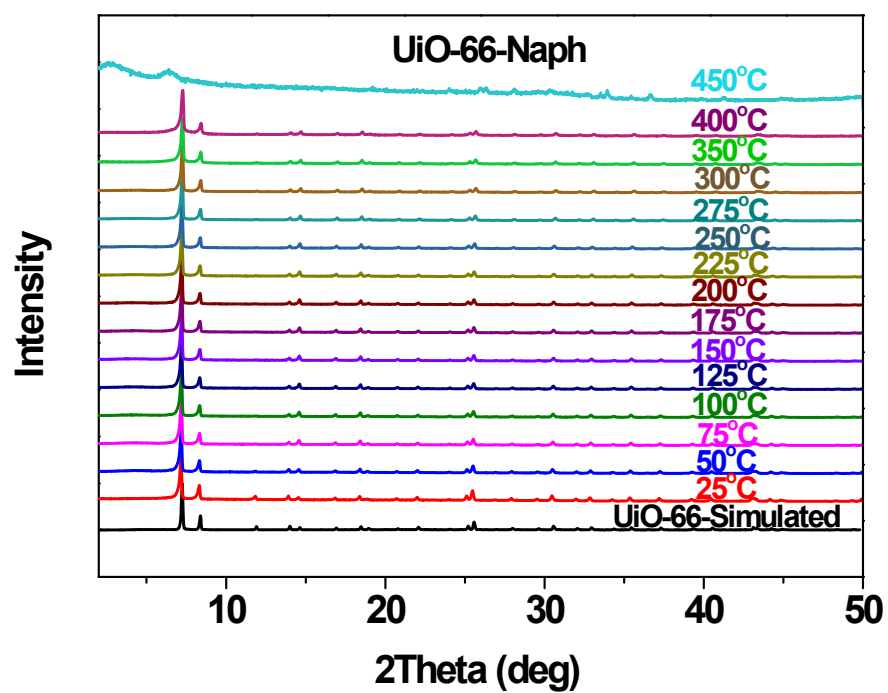


Figure S11. The variable-temperature PXRD patterns of UiO-66-Naph.

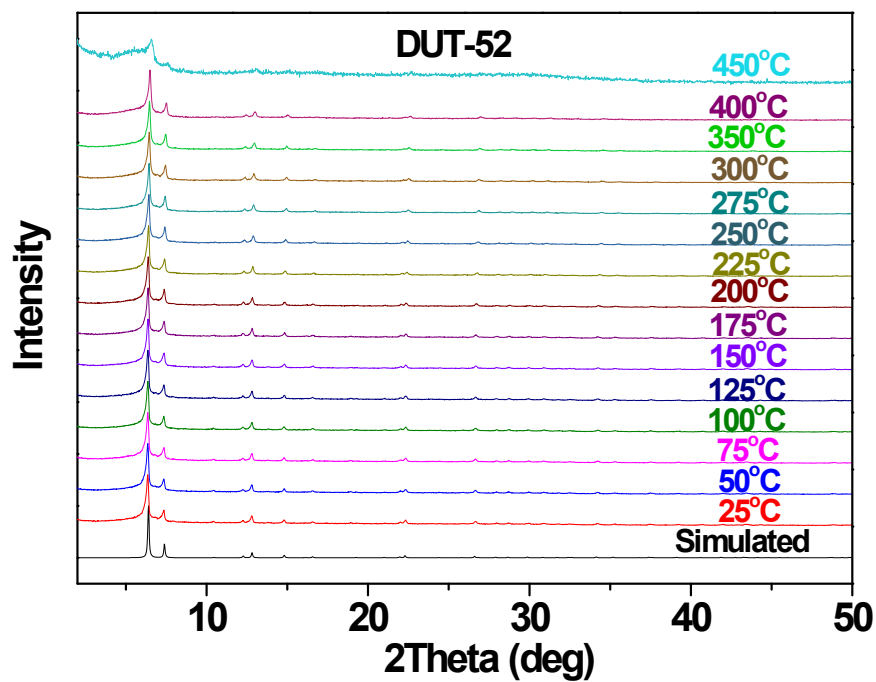


Figure S12. The variable-temperature PXRD patterns of DUT-52.

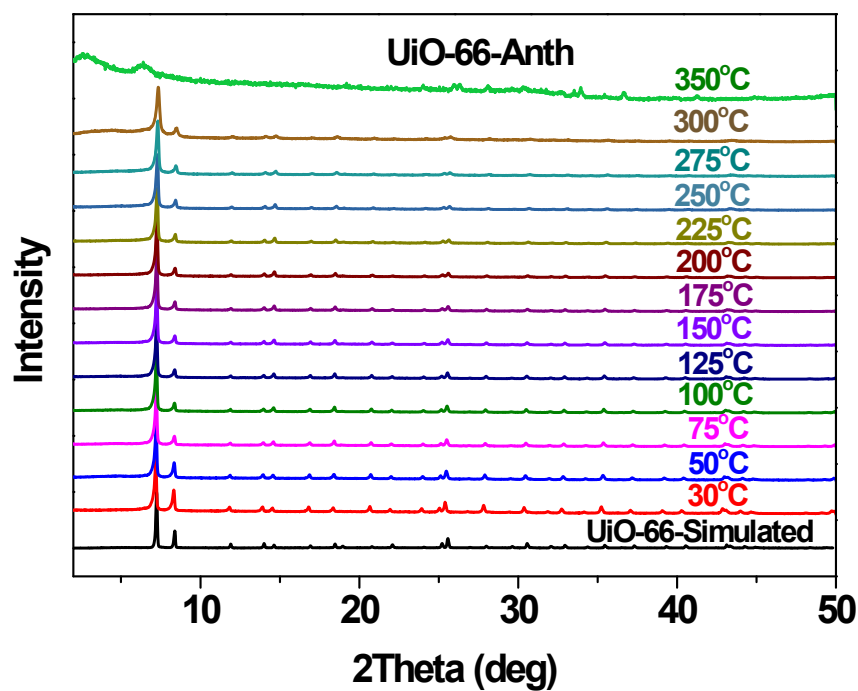


Figure S13. The variable-temperature PXRD patterns of UiO-66-Anth.

S4. Porosity Characterization

N₂ Sorption Isotherm at 77 K: Before gas sorption experiments, the four as-synthesized MOFs and the sample after chemical stability test were immersed in anhydrous acetone for 3 days, during which the solvent was decanted and freshly replenished 3 times a day. The solvent-exchanged samples of the MOFs were activated under vacuum at 100°C for 12 hours. N₂ adsorption isotherms for pressures in the range of 0-1.0 bar were collected by a volumetric method using a quantachrome autosorb IQ3 gas adsorption analyzer. The pore size distribution of UiO-66-Anth is put in Figure S14. The N₂ adsorption isotherms of the MOFs after chemical stability test are showed in Figure S15-Figure S18. BET surface area (m² g⁻¹) of four MOFs after treatment are present in **Table S1**. The BET calculation fittings are plotted in Figure S19-Figure S22. The porosity parameters of MOFs are summarized in **Table S4**. The model settings for calculating pore distributions of the MOFs are as follows: 1) UiO-66: N₂ at 77 K on carbon (slit/cylinder/sphere. pores, QSDFT adsorption branch); 2) UiO-66-Naph: N₂ at 77 K on carbon (slit/cylinder/sphere. pores, QSDFT adsorption branch); 3) DUT-52: N₂ at 77 K on carbon (slit/cylinder/sphere. pores, QSDFT adsorption branch); 4) UiO-66-Anth: N₂ at 77 K on carbon (slit/cylinder/sphere. pores, QSDFT adsorption branch).

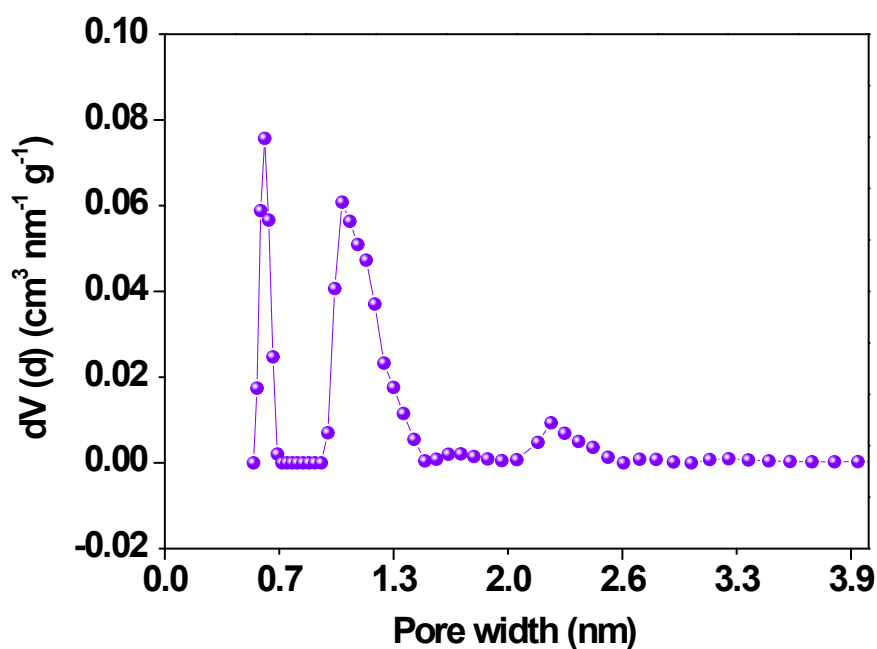


Figure S14. Pore size distribution of UiO-66-Anth calculated from QSDFT mode.

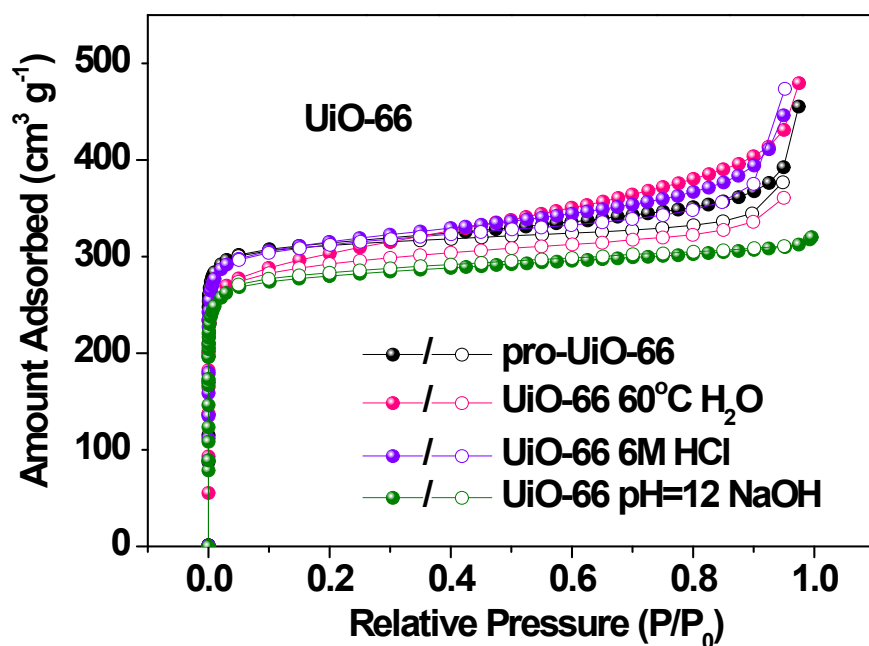


Figure S15. N₂ adsorption isotherms of UiO-66 immersed in 6M HCl, pH = 12 NaOH and 60 °C water for 24 h at 77 K. (Filled symbols, adsorption; empty symbols, desorption.)

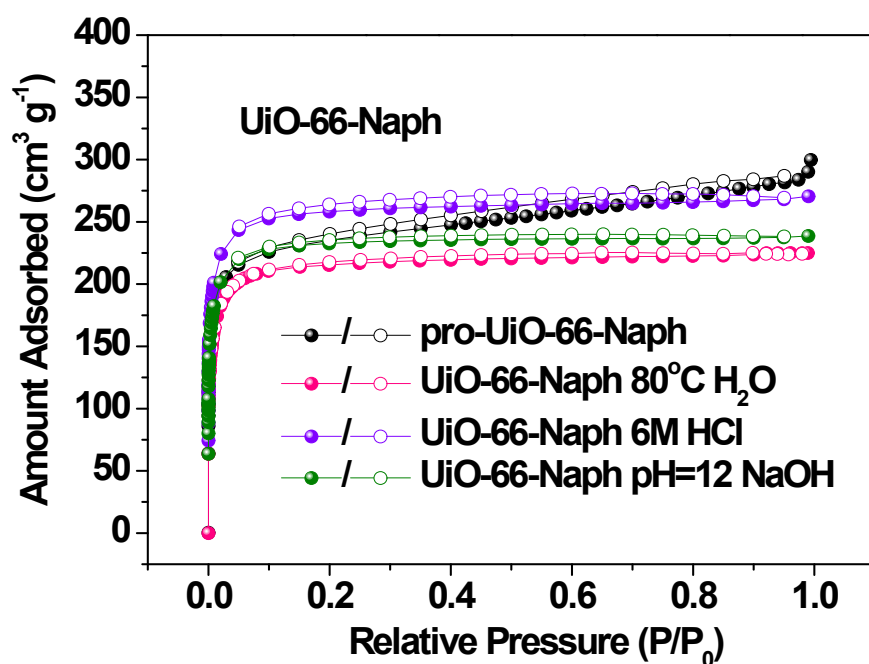


Figure S16. N₂ adsorption isotherms of UiO-66-Naph immersed in 6M HCl, pH = 12 NaOH and 80 °C water for 24 h at 77 K. (Filled symbols, adsorption; empty symbols, desorption.)

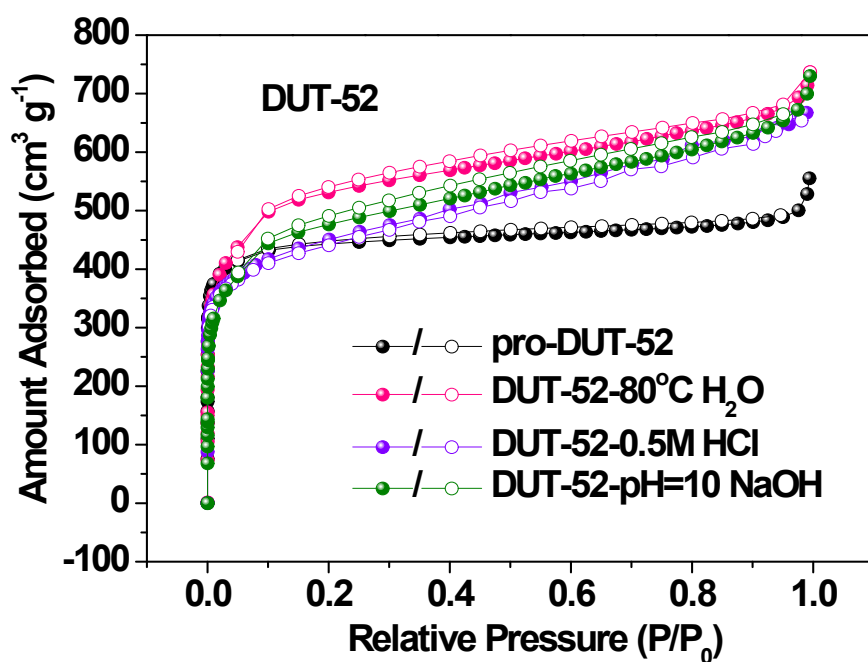


Figure S17. N₂ adsorption isotherms of DUT-52 immersed in 0.5 M HCl, pH = 10 NaOH and 80 °C water for 24 h at 77 K. (Filled symbols, adsorption; empty symbols, desorption.)

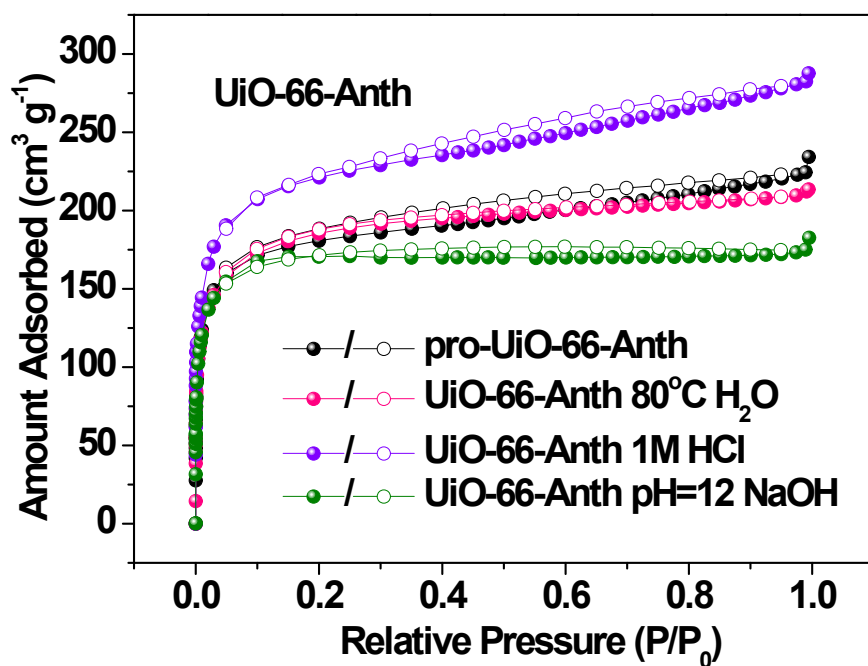


Figure S18. N₂ adsorption isotherms of UiO-66-Naph immersed in 1M HCl, pH = 12 NaOH and 80 °C water for 24 h at 77 K. (Filled symbols, adsorption; empty symbols, desorption.)

Table S1. BET surface area ($\text{m}^2 \text{g}^{-1}$) of four MOFs after treatment.

MOF Treatment	MOF			
	UiO-66	UiO-66-Naph	DUT-52	UiO-66-Anth
Origin	1305	881	1671	676
80 °C H ₂ O	1232 ^a	883	1613	695
HCl	1239 ^b	908 ^b	1635 ^c	641 ^d
pH = 12 NaOH	1117	834	1579 ^e	664

^a60 °C. ^b6 M HCl. ^c0.5 M HCl. ^d1 M HCl. ^epH = 10 NaOH.

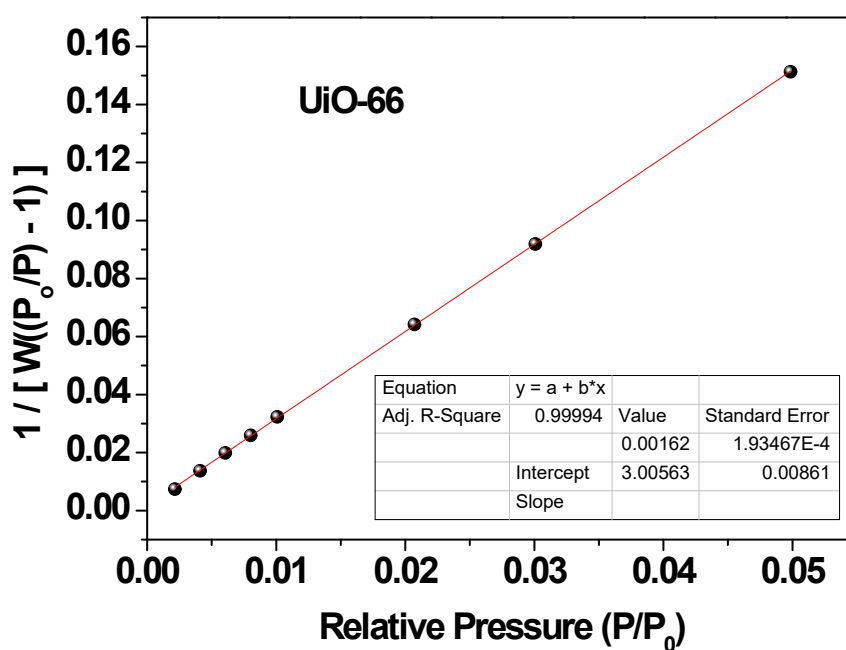


Figure S19. Plot of the linear region on the N₂ isotherm of UiO-66 for the BET equation.

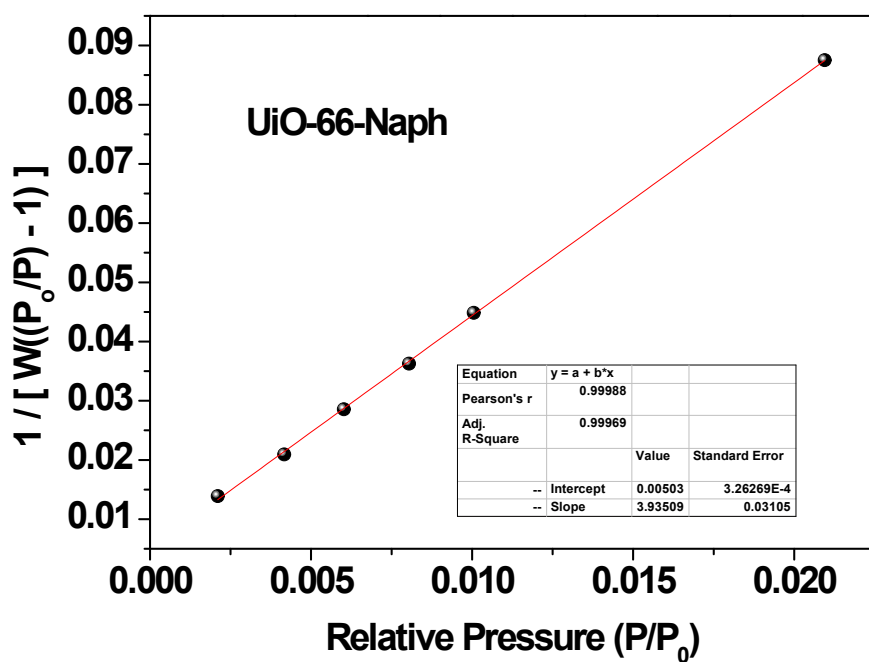


Figure S20. Plot of the linear region on the N₂ isotherm of UiO-66-Naph for the BET equation.

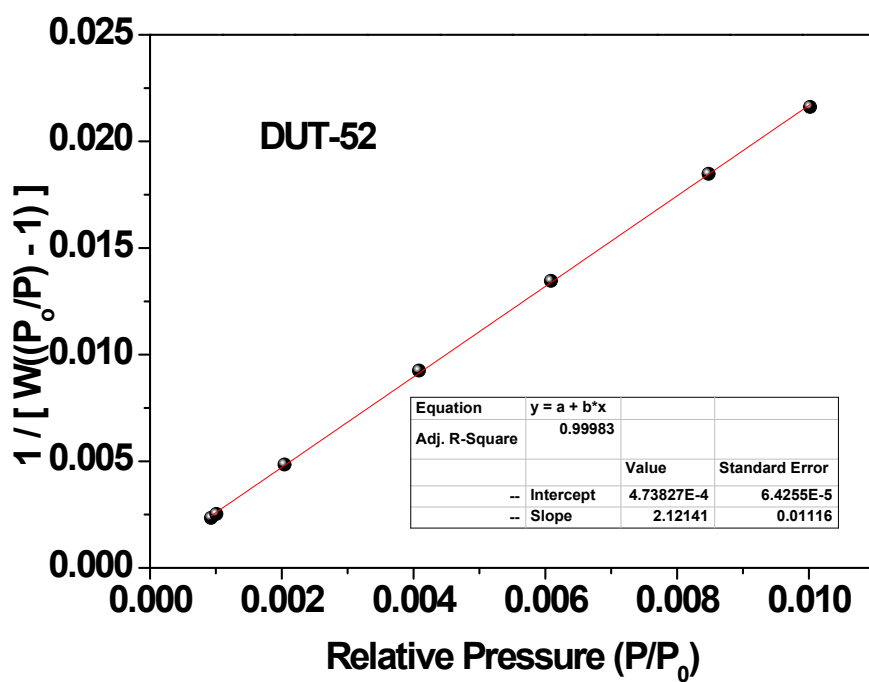


Figure S21. Plot of the linear region on the N₂ isotherm of DUT-52 for the BET equation.

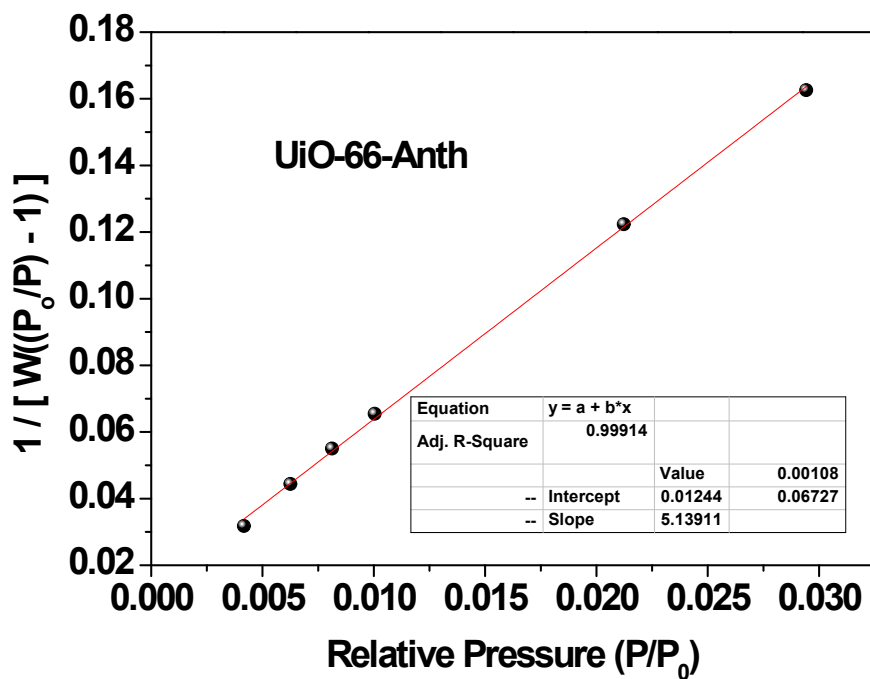


Figure S22. Plot of the linear region on the N_2 isotherm of UiO-66-Anth for the BET equation.

S5. Calculations of Adsorption Isosteric Heat

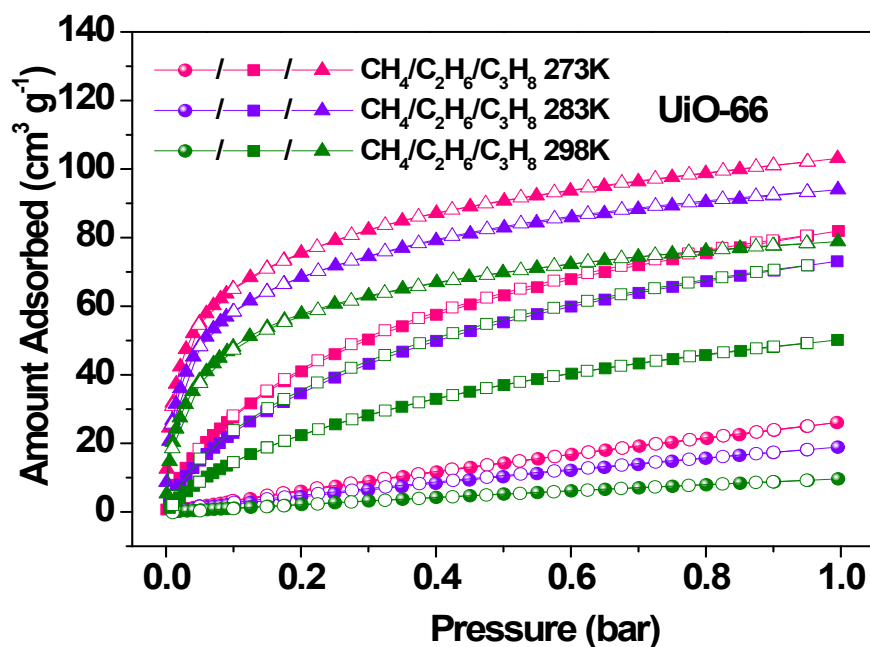


Figure S23. CH_4 , C_2H_6 and C_3H_8 adsorption isotherms of UiO-66 at 273, 283 and 298K. (Filled symbols, adsorption; empty symbols, desorption.)

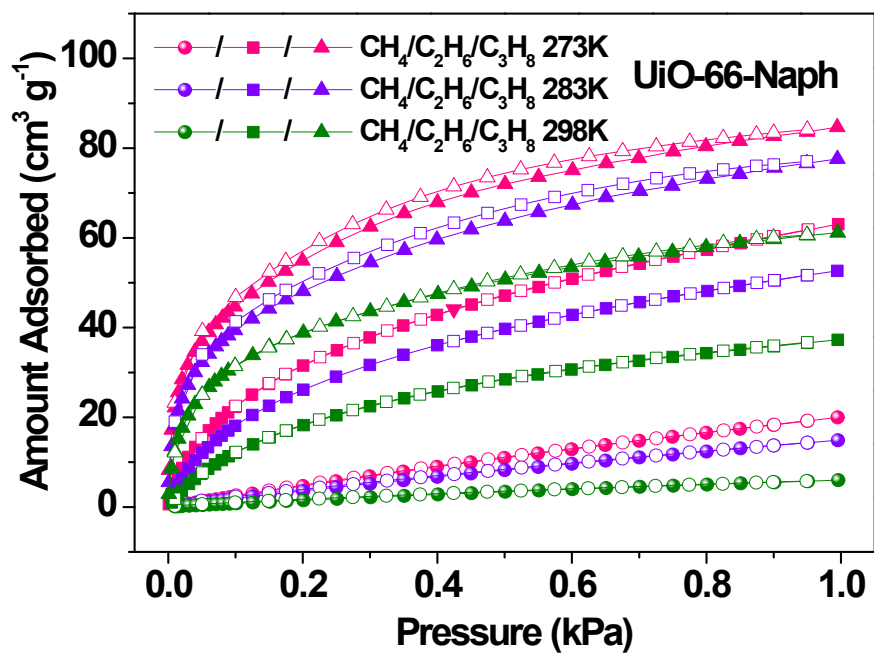


Figure S24. CH₄, C₂H₆ and C₃H₈ adsorption isotherms of UiO-66-Naph at 273, 283 and 298K. (Filled symbols, adsorption; empty symbols, desorption.)

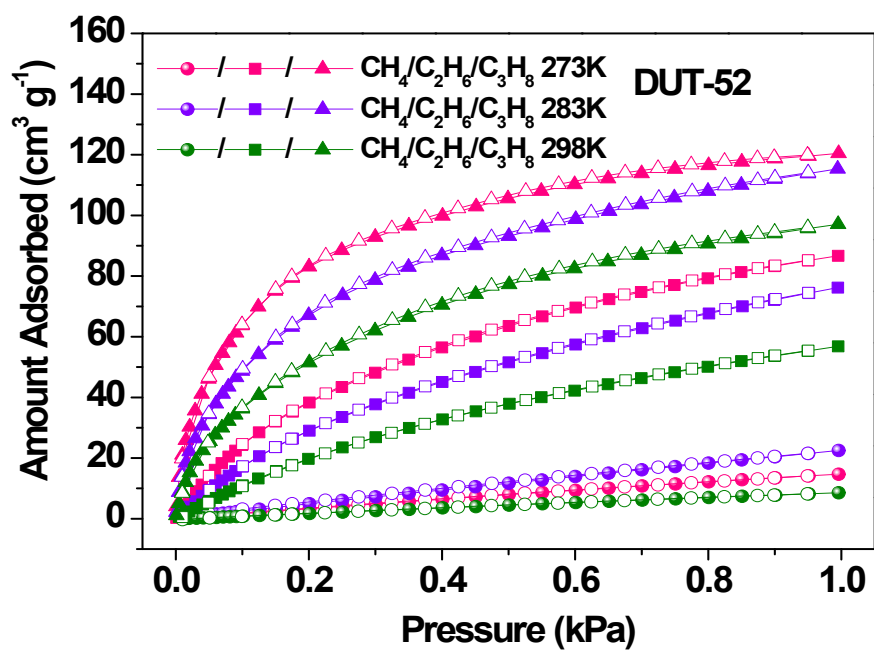


Figure S25. CH₄, C₂H₆ and C₃H₈ adsorption isotherms of DUT-52 at 273, 283 and 298K. (Filled symbols, adsorption; empty symbols, desorption.)

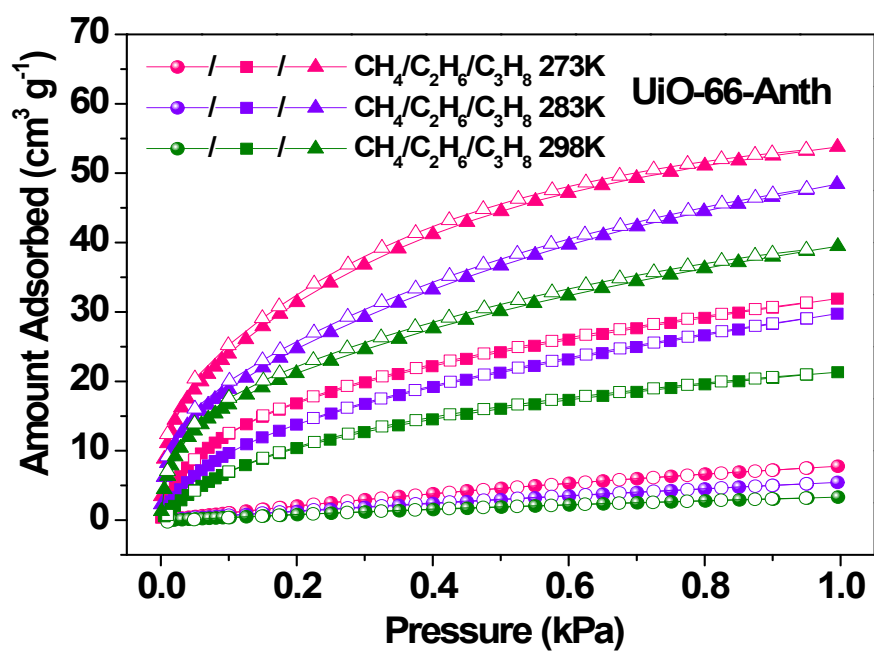


Figure S26. CH₄, C₂H₆ and C₃H₈ adsorption isotherms of UiO-66-Anth at 273, 283 and 298K. (Filled symbols, adsorption; empty symbols, desorption.)

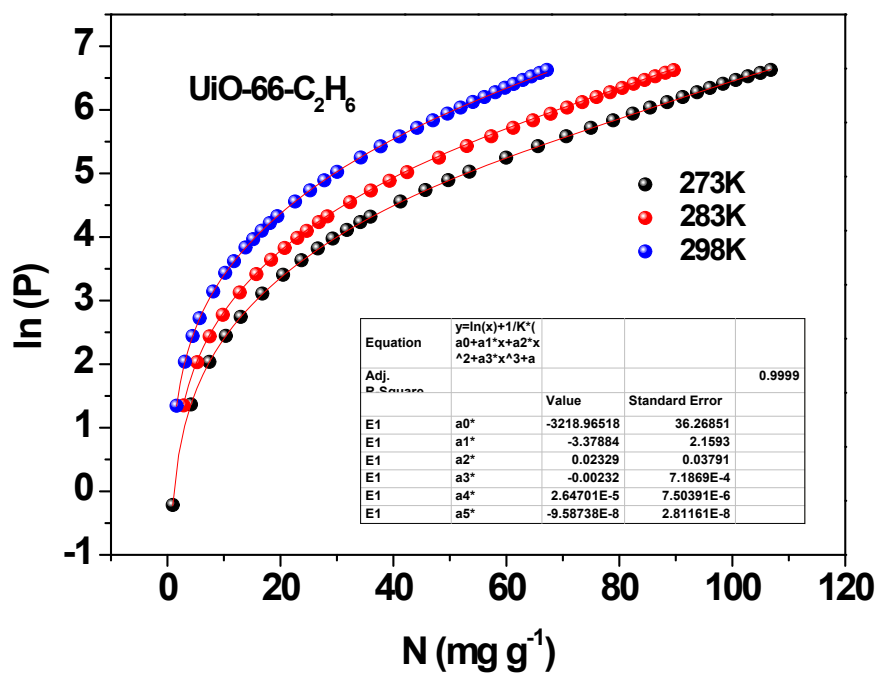


Figure S27. C₂H₆ virial fitting (lines) of the adsorption isotherms (points) of UiO-66 measured at 273, 283 and 298 K.

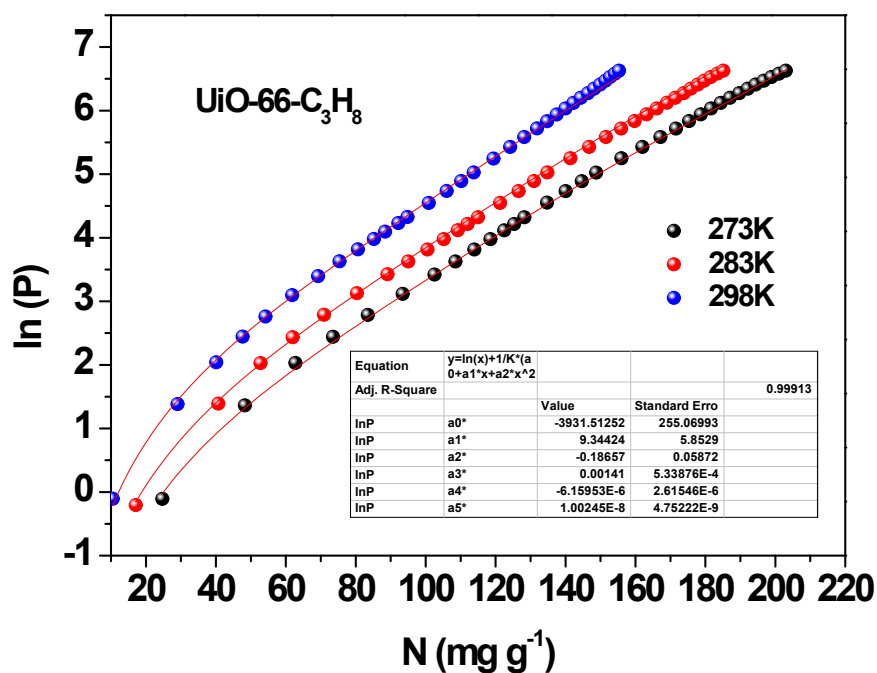


Figure S28. C_3H_8 virial fitting (lines) of the adsorption isotherms (points) of UiO-66 measured at 273, 283 and 298 K.

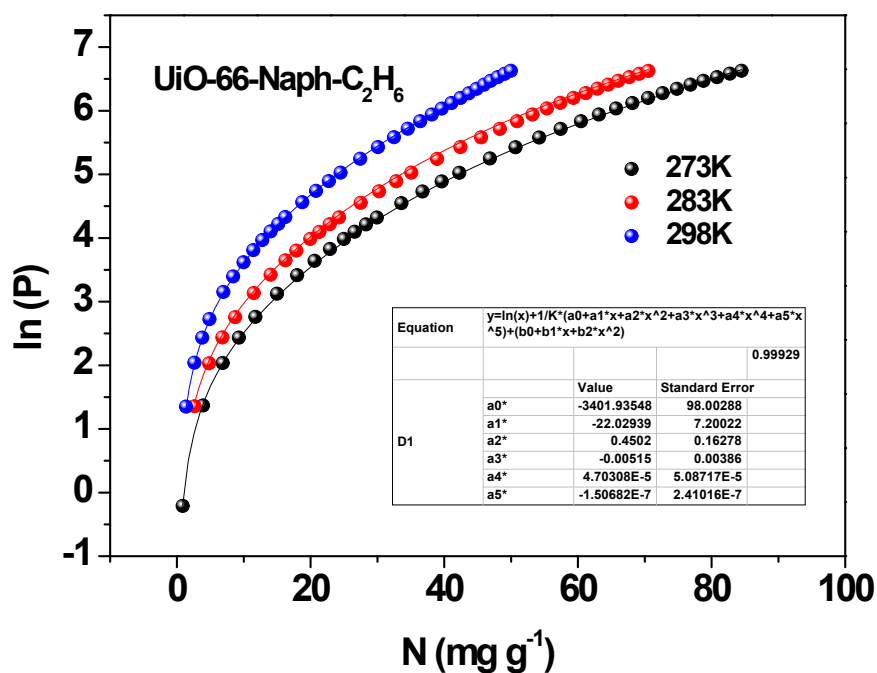


Figure S29. C_2H_6 virial fitting (lines) of the adsorption isotherms (points) of UiO-66-Naph measured at 273, 283 and 298 K.

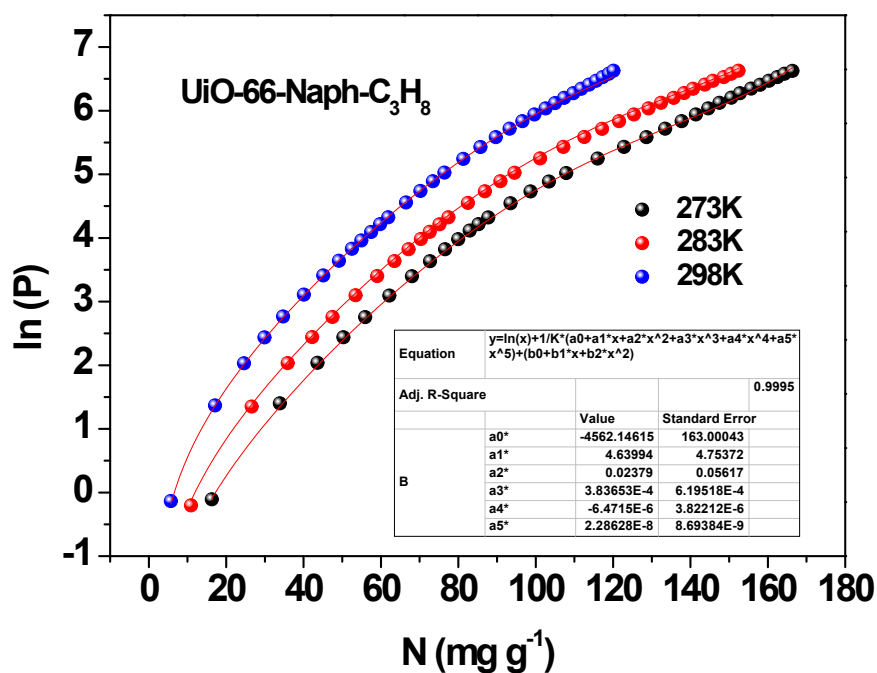


Figure S30. C_3H_8 virial fitting (lines) of the adsorption isotherms (points) of UiO-66-Naph measured at 273, 283 and 298 K.

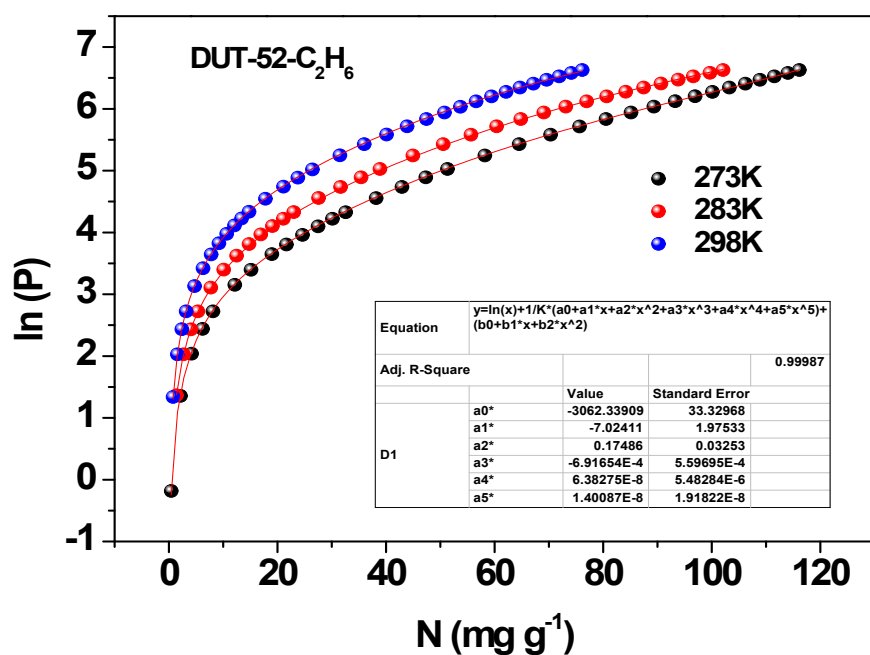


Figure S31. C_2H_6 virial fitting (lines) of the adsorption isotherms (points) of DUT-52 measured at 273, 283 and 298 K.

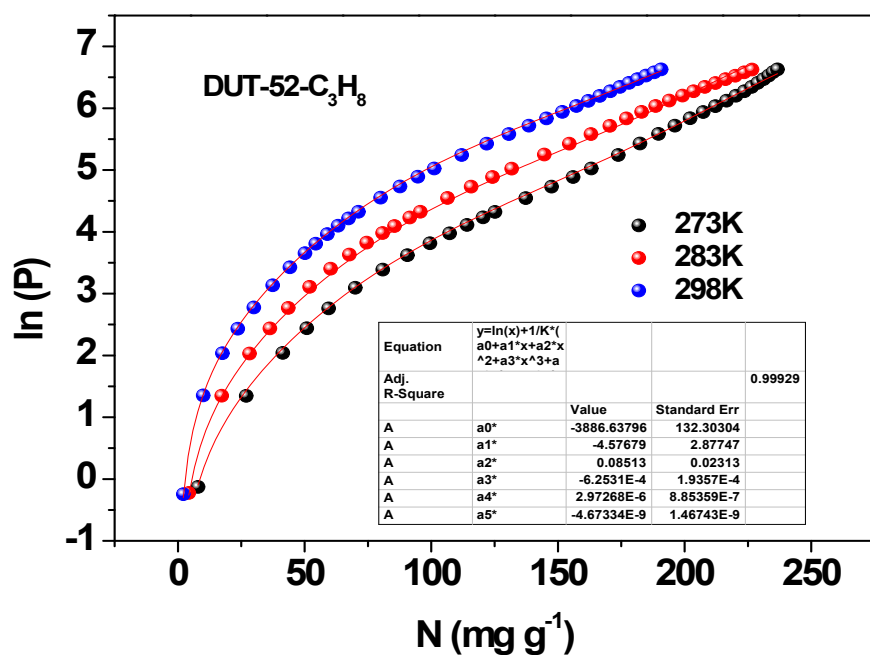


Figure S32. C₃H₈ virial fitting (lines) of the adsorption isotherms (points) of DUT-52 measured at 273, 283 and 298 K.

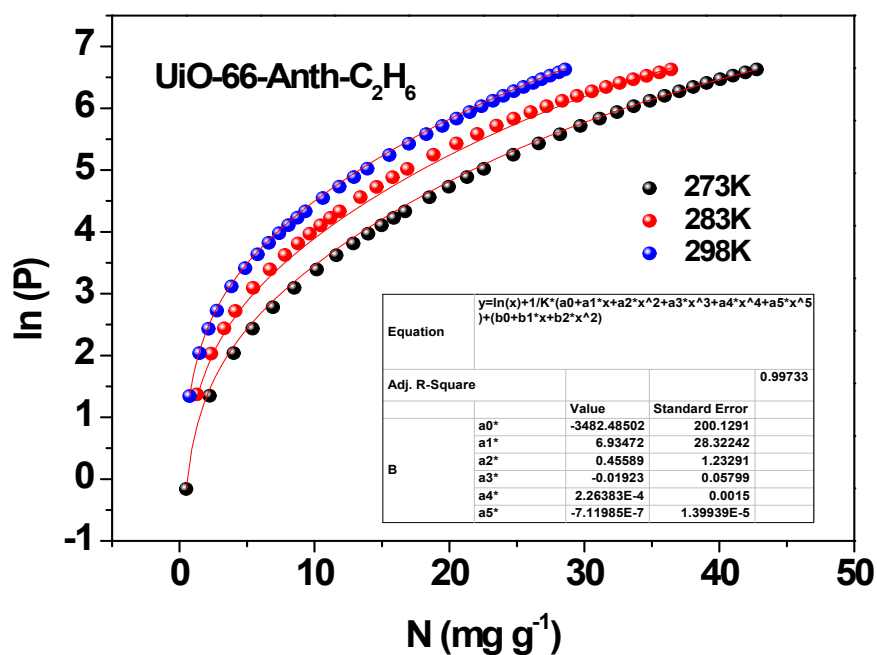


Figure S33. C₂H₆ virial fitting (lines) of the adsorption isotherms (points) of UiO-66-Anth measured at 273, 283 and 298 K.

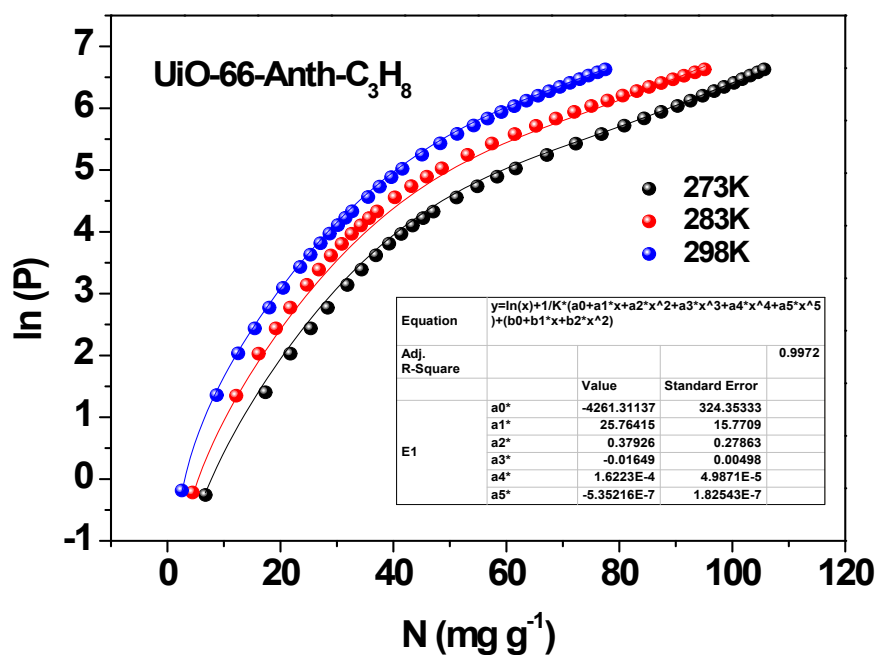


Figure S34. C_3H_8 virial fitting (lines) of the adsorption isotherms (points) of UiO-66-Anth measured at 273, 283 and 298 K.

S6. Comparison of C_3/C_1 IAST Selectivity Enhancing Effects

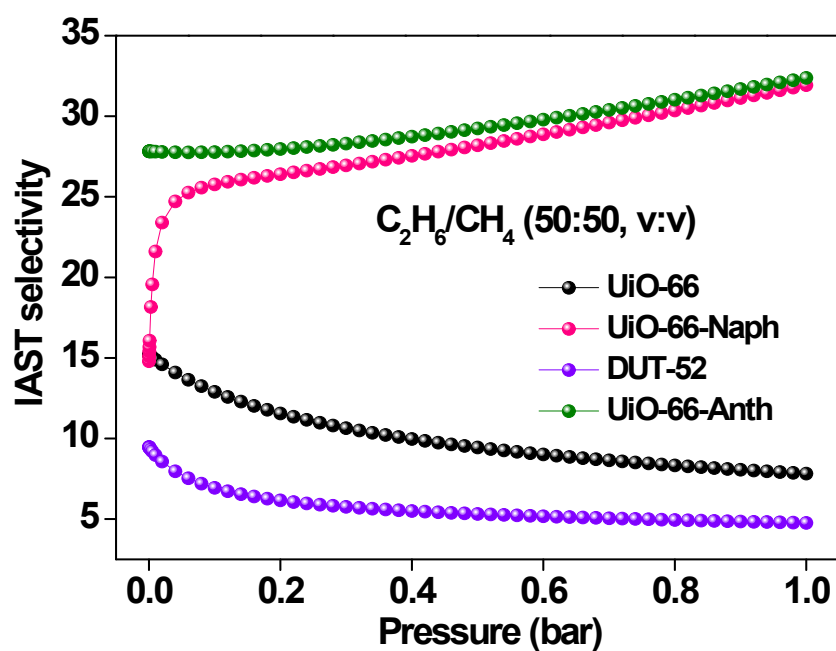


Figure S35. IAST selectivity of the MOFs for $\text{C}_2\text{H}_6/\text{CH}_4$ (50:50, v:v).

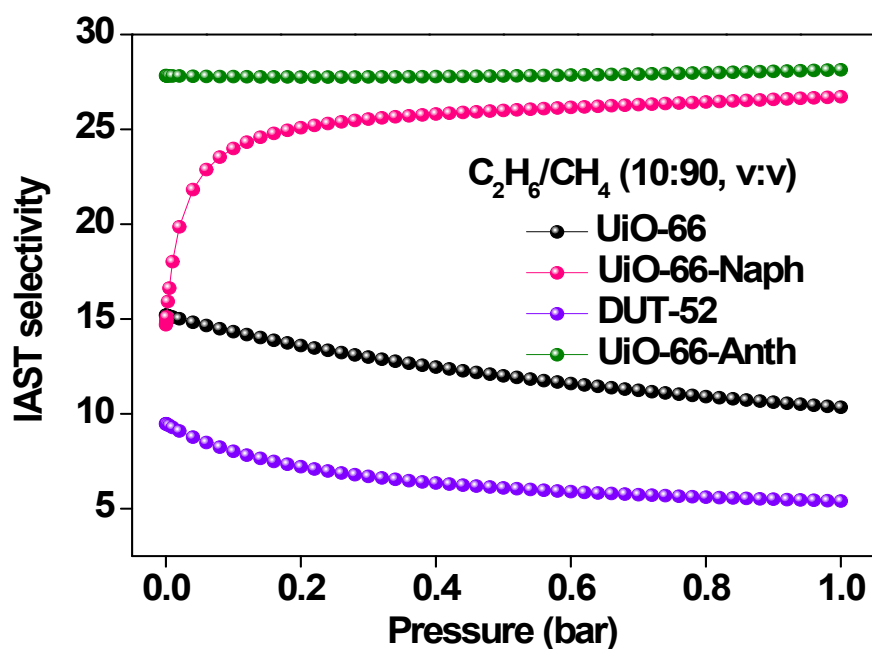


Figure S36. IAST selectivity of the MOFs for C_2H_6/CH_4 (10:90, v:v).

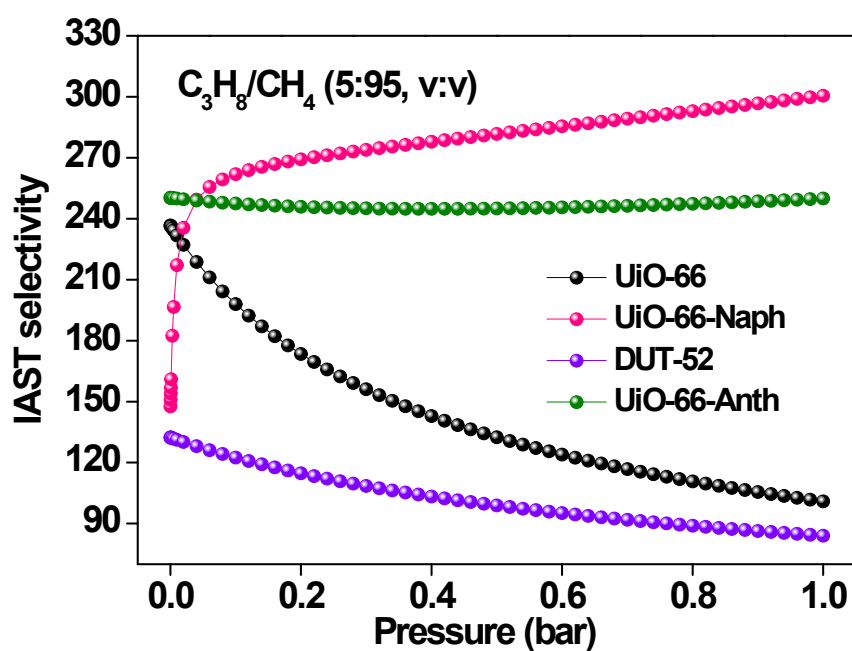


Figure S37. IAST selectivity of the MOFs for C_3H_8/CH_4 (5:95, v:v).

C_3/C_1 IAST selectivity increase are evaluated by the increase ratio, which is calculated by the following equation.

C_3/C_1 IAST selectivity increase ratio

$$= \frac{\text{improved IAST selectivity} - \text{original IAST selectivity}}{\text{original IAST selectivity}} \times 100\%$$

Table S2. Comparison of C₃/C₁ IAST selectivity increase effects in porous materials.

C ₃ /C ₁ IAST Enhancing Effect	Selectivity	MOFs	C ₃ /C ₁ IAST selectivity (50:50)	C ₃ /C ₁ IAST selectivity increase ratio (50:50)	Reference
Aromatic effect		UiO-66	65	0	This work
		UiO-66-Naph	741	1040%	
		DUT-52	48	-26%	
		UiO-66-Anth	535	723%	
Macrocyclic effect		P5-CMP-1	180 ^a	0	1
		P5-CMP-2	189 ^a	5%	
Configurations effect (①/②,③/④); Pore size effect (①/③, ②/④)		①sPI-A-H	66.4		2
		②sPI-M-H	82.0		
		③sPI-A-B	204.7		
		④sPI-M-B	217.4		
Functional group effect		MPI	284	205%	3
		MPI-S	93	0	
		MPI-Ag	94	1%	
Fluorine-functionalization effect		PAN-5H	176.2	0	4
		PAN-5F	372.3	111%	
		PAN-2F	260.5	48%	
		PAN-2(CF) ₃	198.1	12%	
Monomers size effect		PAN-T1	190.8 ^a	37%	5
		PAN-T2	139.0 ^a	0	
Donor position effect		eea-MOFs	136 ^b	0	6
		rtl-MOFs	156 ^b	15%	
Coordination modes effect		JLU-Liu5	107.8 ^b	0	7
		JLU-Liu6	274.6 ^b	155%	
Temperature effect (400,500,600 °C)		ZnP-CTF-400	290	0	8
		ZnP-CTF-500	513	77%	
		ZnP-CTF-600	733	153%	
Temperature effect (500,550,600 °C)		CTF-BIB-1	386.6	127%	9
		CTF-BIB-2	311.2	82%	
		CTF-BIB-3	170.5	0	
Temperature effect (600,700,800 °C)		NAC 600	406.0	99%	10
		NAC 700	501.9	147%	
		NAC 800	203.6	0	

Regulator effect	Zn2(TCPP)(DPB)	122.3	195%	11
	(1)	41.4	0	
	Zn2(TCPP)(DPB) (2)			
Metal ion effect	LIFM-13(Mg)	528.9	314%	12
	LIFM-13(Co)	161.5	26%	
	LIFM-13(Ni)	252.2	97%	
	LIFM-13(Zn)	127.8	0	
Metalloporphyrin effect (110kPa)	PAF-40	48.2	0	13
	PAF-40-Fe	56	16%	
	PAF-40-Mn	246	410%	

^aThe C₃/C₁ ratio is 10:90. ^bThe C₃/C₁ ratio is 5:95.

Table S3. CH₄/C₂H₆/C₃H₈ adsorption and separation performance for some benchmark adsorbents at 298 K and 100 kPa.

MOFs	CH ₄ (mmol ⁻¹)	C ₂ H ₆ (mmol ⁻¹)	C ₃ H ₈ (mmol ⁻¹)	C ₃ /C ₁ IAST selectivity (298K, 50:50)	C ₂ /C ₁ IAST selectivity (298K, 50:50)	Reference
UiO-66	0.60	1.67	1.79	65	8	This work
UiO-66-Naph	0.38	1.24	1.39	741	32	
DUT-52	0.54	1.89	2.21	48	5	
UiO-66-Anth	0.21	0.70	0.90	535	32	
ANPC-1-800	1.45	6.84	9.74	110.4	14.5	14
ANPC-2-700	1.12	4.88	8.80	162.5	13.5	
ANPC-2-800	1.15	4.94	11.5	120.2	11.9	
BSF-1	0.66	1.17	0.99	353	23	15
FJI-C4	1.15	2.21	1.63	293.4	39.7	16
FJI-H22	0.88	1.49	1.10	145.23	11.95	17
JLU-Liu5	1.00	2.37	1.59	107.8	17.6	7
JLU-Liu6	0.81	1.63	1.30	274.6	20.4	
JLU-Liu7	1.06	3.57	2.57	128.5	50.4	18
JLU-Liu38	0.48	4.96	8.39	98	12.5	19
JUC-100	0.64	3.07	3.09	80	11	20
JUC-103	0.73	2.85	2.77	55	8	
JUC-106	0.51	2.61	2.59	75	13	
UTSA-35a (296K)	0.43	2.43	2.97	80	20	21
MFM-202a	0.45	4.21	6.76	87	10	22
InOF-1	0.64	4.14	4.25	90	17	23
RT-MIL-100(Fe)	0.36	2.22	6.78	33.3(5:85)	6(10:85)	24
MIL-101-Cr	0.49	1.59	3.35	84.3	22.5	25
MIL-101-Fe	0.45	1.25	3.29	24.9	15.4	
MIL-101-Fe-NH ₂	0.46	1.35	3.32	42.5(5:85)	11.6(10:85)	
A-AC-3	1.38	7.09	11.34	76.6(1:4)	16.9(1:4)	26
A-AC-4	1.18	6.59	11.76	88.8(1:4)	15.1(1:4)	
A-AC-5	0.98	5.00	9.12	9.31(Uptake ratio)	5.10(Uptake ratio)	
sPI-A-H	0.39	1.59	2.00	66.7	13.3	2
SBA-15	0.11	0.56	1.24	/	4.9(Uptake ratio,303K)	27

S7. Breakthrough Experiments

Transient breakthrough experiments for the separation of CH₄/C₂H₆/C₃H₈ (85:10:5, v:v:v) were carried out in a fixed bed. The column (6 mm inner diameter × 150 mm) was filled with ~1g pre-activated sample for the experiment using a ternary component gases mixture. Before filled in the column, the samples were activated at 373 K for 8 h under vacuum conditions. After filling the column, the column was purged with a He flow for 1 h. The flow rates (5 mL min⁻¹ at 298 K and 1 bar) of gases were regulated by mass flow controllers. Then the CH₄/C₂H₆/C₃H₈ gas mixture with 5 mL min⁻¹ was introduced to the column. The outlet composition was continuously monitored by a gas chromatograph (FULI GC9790 Plus) until a complete breakthrough was achieved. The sample was regenerated with a He flow (5 mL min⁻¹) at 373 K for 2 h before each cyclic experiment.

The capture capacity (also called capture amount) is determined as follows:^{28, 29}

$$q_i = \frac{v \times V_i\%}{22.4 \times m} \int_0^t \left(1 - \frac{C}{C_0}\right) dt$$

Where q_i is the capture amount of gas i (mmol g⁻¹), v is the flow rate of the gas mixture (mL min⁻¹), $V_i\%$ is molar fraction of gas i , t is the adsorption time (min), C_0 and C are the inlet and outlet gas concentration, respectively, and m is the mass of the adsorbent (g).

The separation potential (Δq) represents the difference of moles of component 1 (the more strongly adsorbed gas) and component 2 (the less strongly adsorbed gas) adsorbed in the per g of adsorbents in the fixed bed. Δq is calculated by following the equation below proposed by Krishna.^{30, 31}

$$\Delta q = q_1 - q_2 \frac{y_1}{y_2}$$

Where q_1 and q_2 are the capture amount (units: mmol g⁻¹) for mixture adsorption, calculated from the breakthrough curves, respectively, and y_1 and y_2 are the component content of the gases.

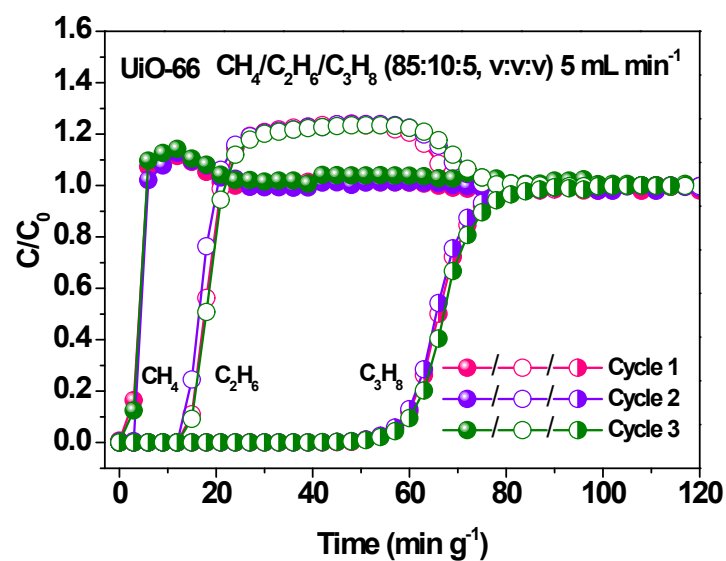


Figure S38. Three cycles of transient breakthrough tests of a $\text{CH}_4/\text{C}_2\text{H}_6/\text{C}_3\text{H}_8$ (85:10:5, v:v:v) mixture for UiO-66.

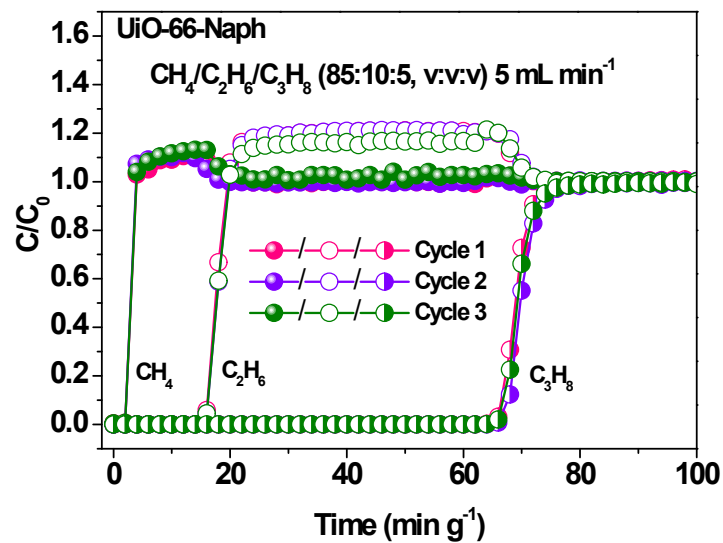


Figure S39. Three cycles of transient breakthrough tests of a $\text{CH}_4/\text{C}_2\text{H}_6/\text{C}_3\text{H}_8$ (85:10:5, v:v:v) mixture for UiO-66-Naph.

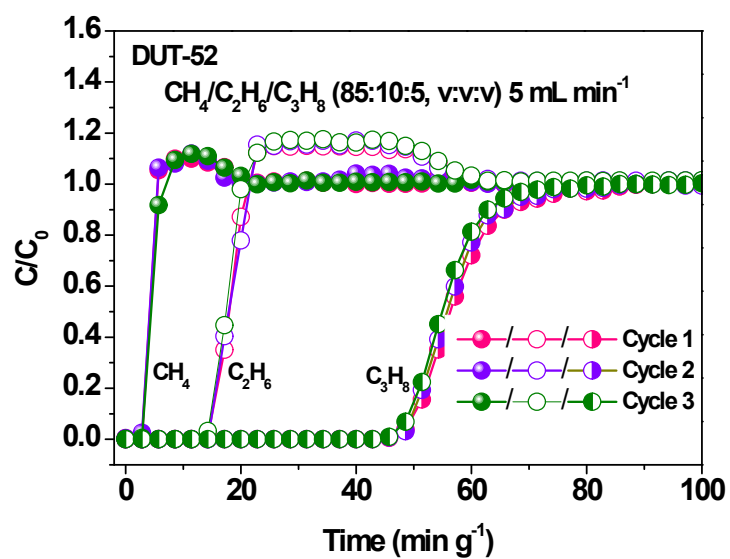


Figure S40. Three cycles of transient breakthrough tests of a $\text{CH}_4/\text{C}_2\text{H}_6/\text{C}_3\text{H}_8$ (85:10:5, v:v:v) mixture for DUT-52.

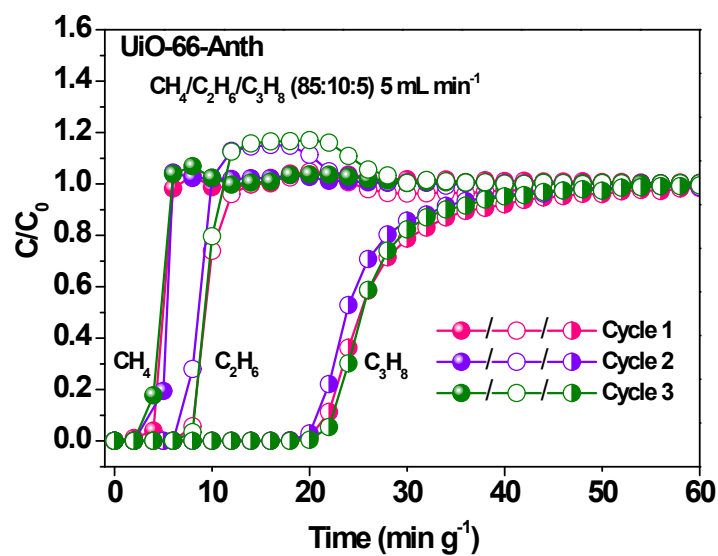


Figure S41. Three cycles of transient breakthrough tests of a $\text{CH}_4/\text{C}_2\text{H}_6/\text{C}_3\text{H}_8$ (85:10:5, v:v:v) mixture for UiO-66-Anth.

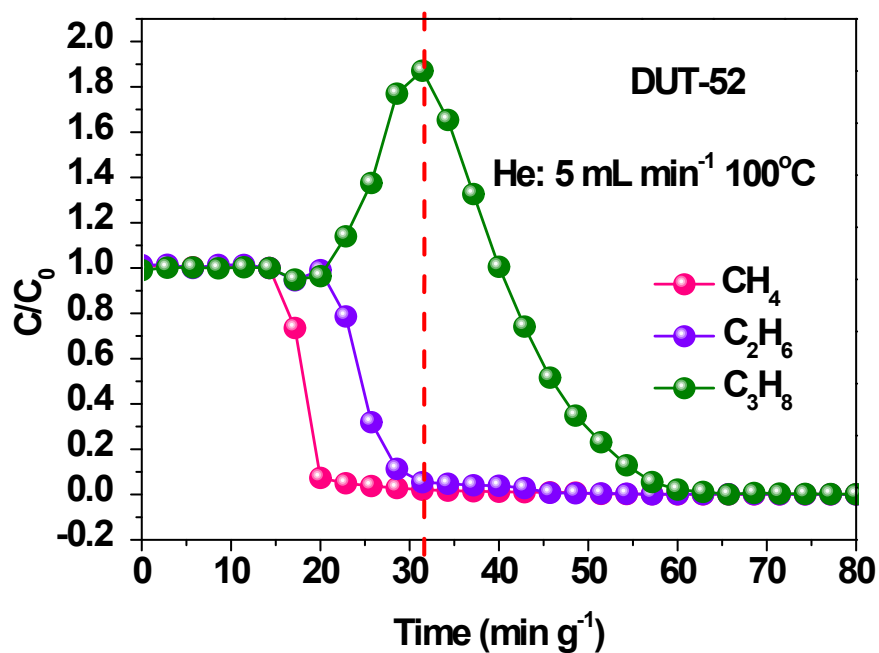


Figure S42. Desorption curves of DUT-52 for the $\text{CH}_4/\text{C}_2\text{H}_6/\text{C}_3\text{H}_8$ (85:10:5, v:v:v) mixture separation.

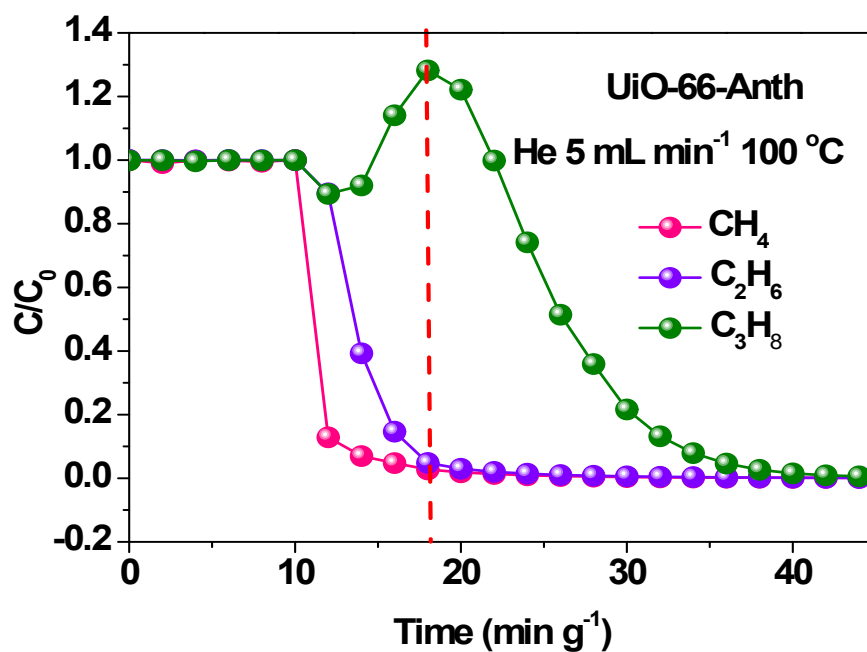


Figure S43. Desorption curves of UiO-66-Anth for the $\text{CH}_4/\text{C}_2\text{H}_6/\text{C}_3\text{H}_8$ (85:10:5, v:v:v) mixture separation.

Table S4. Summary of MOF BET surface areas, pore volumes, C_2/C_1 & C_3/C_1 IAST selectivities, isosteric heats (Q_{st}), breakthrough productivities (for CH_4), breakthrough capture capacities (for C_2H_6 and C_3H_8) and separation potentials (Δq for C_3H_8/CH_4).

MOF	BET surface area (m ² g ⁻¹)	V _p (cm ³ g ⁻¹)	Pore size (nm)	C ₂ /C ₁	C ₃ /C ₁	Q _{st} (kJ mol ⁻¹)		Breakthrough	Breakthrough		Δq(C ₃ H ₈ / CH ₄)
				IAST	IAST			productivity	capture capacity		
				selectivity (10: 95 / 50: 50)	selectivity (5: 95 / 50: 50)	C ₂ H ₆	C ₃ H ₈	CH ₄	C ₂ H ₆	C ₃ H ₈	
UiO-66	1305	0.47	0.86,1.11	10/ 8	100/ 65	26.76	32.69	1.65	0.18	0.74	0.71
UiO-66-Naph	881	0.40	0.55,1.05	26/ 32	300/ 741	28.29	37.92	2.25	0.18	0.77	0.75
DUT-52	1641	0.70	1.03,1.73	6/ 5	84/ 48	24.57	28.89	2.08	0.28	0.63	0.20
UiO-66-Anth	676	0.32	0.57,1.01	28/ 32	250/535	28.95	35.16	0.17	0.15	0.29	0.61

S8. Theoretical Calculations

Grand canonical Monte Carlo (GCMC) calculations were performed with the Sorption module of Materials Studio.³² One unit cell was used. Four H^+ is add to each Zr_6O_8 cluster to balance the charge.³³ The MOF structures are all optimized with the Forcite module using Universal force field (UFF). The charges were determined by the charge equilibration (QEq) approach.³⁴ The structures and charges of CH_4 , C_2H_6 , and C_3H_8 were prepared with Dmol³ module (Figure S45).³⁵ The Perdew-Burke-Ernzerhof (PBE) functional was used under the generalized gradient approximation (GGA) functional with the double- ξ numerical polarization (DNP) basis set. The tolerances of energy, gradient, and displacement convergence were 1.0×10^{-5} hartree, 2×10^{-3} hartree $\text{\AA}^{-1}$, and 5×10^{-3} $\text{\AA}$, respectively. The density distribution of the gases on the MOFs were calculated using the fixed pressure task mode of Sorption module under 298K and 100 kPa (CH_4 fugacity: 99.78 kPa; C_2H_6 fugacity: 99.17 kPa; C_3H_8 fugacity: 98.36 kPa). The frameworks were assumed as rigid. DREIDING force field was used and the parameters of Zr are adopted from Universal force field. A total of 1×10^6 equilibration steps and 1×10^7 production steps were set. The van der Waals interactions were calculated by the atom-based method with a fine cutoff distance of

18.5 Å, whereas the Coulombic interactions were summed by the Ewald and group method.

The primary binding site and simulated isosteric heat (Q_{st}) values were calculated using the Adsorption Locator module. All the sets are similar to the sorption calculations.

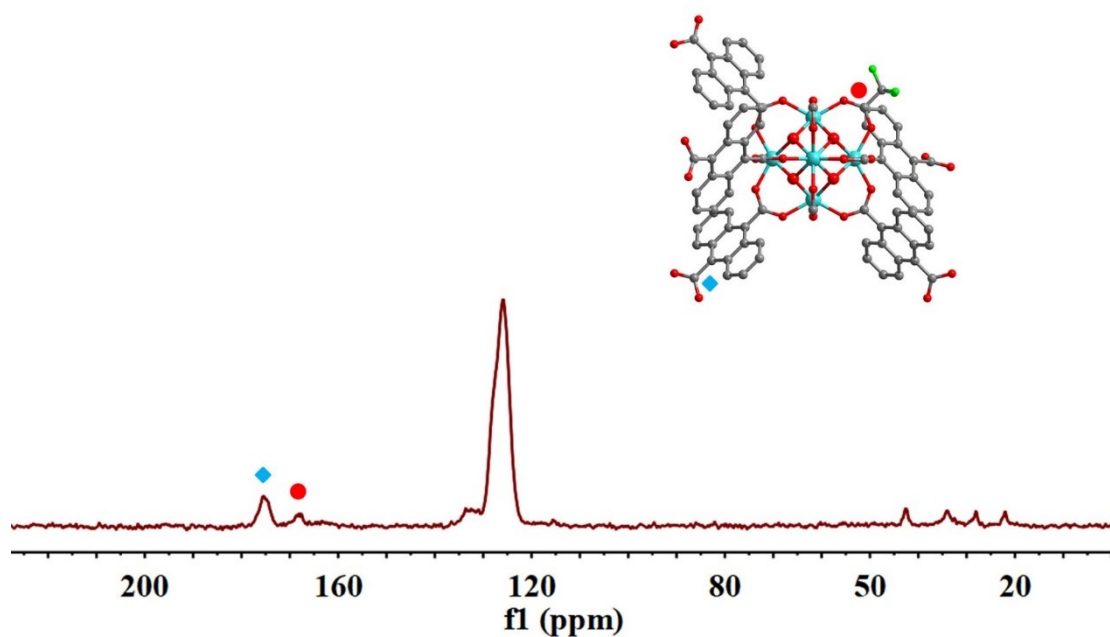


Figure S44. The solid-state ^{13}C NMR spectrum of UiO-66-Anth.

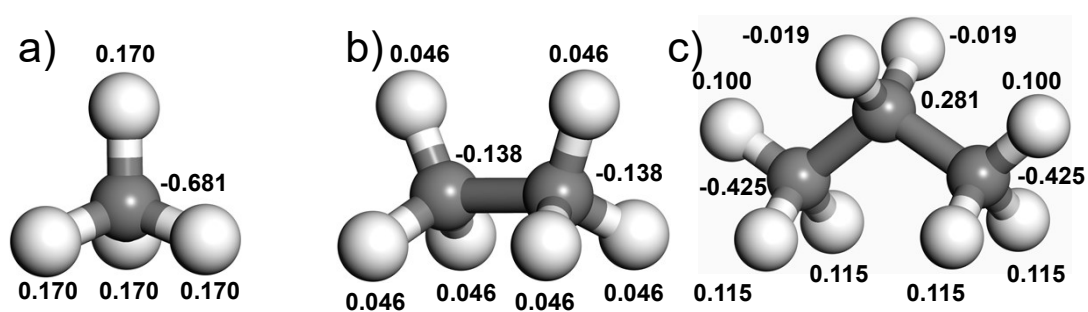


Figure S45. The ESP charges of a) CH_4 , b) C_2H_6 and c) C_3H_8 .

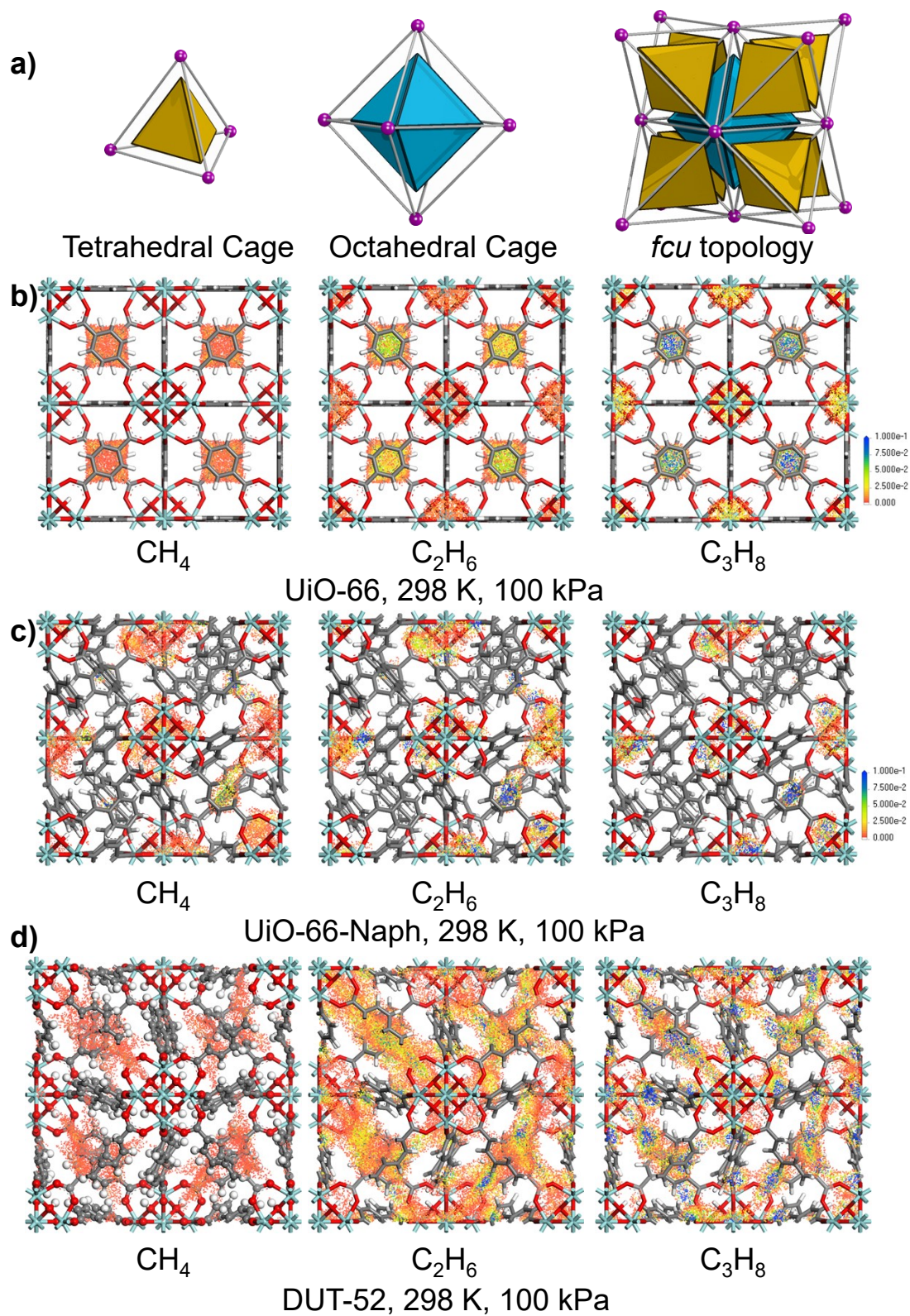


Figure S46. a) The pore structure and topology of UiO-66s. Density distribution of $\text{CH}_4/\text{C}_2\text{H}_6/\text{C}_3\text{H}_8$ in b) UiO-66, c) UiO-66-Naph and d) DUT-52 under 298K and 100 kPa, respectively.

Table S5. The simulated adsorption capacities (100 kPa), experimental adsorption capacities (100 kPa), calculated Q_{st} at primary adsorption site and experimental Q_{st} at zero coverage of UiO-66, UiO-66-Naph and DUT-52 for CH₄/C₂H₆/C₃H₈ adsorption.

MOF	Gas	Simulated adsorption capacities at 100 kPa (cm ³ g ⁻¹)	Experimental adsorption capacities at 100 kPa (cm ³ g ⁻¹)	Simulated Q_{st} (kJ mol ⁻¹)	Experimental Q_{st} (kJ mol ⁻¹)
UiO-66	CH ₄	13.72	9.64	18.9	-
	C ₂ H ₆	36.13	50.15	23.5	26.8
	C ₃ H ₈	39.37	78.87	43	34.3
UiO-66-Naph	CH ₄	13.43	6.01	23.5	-
	C ₂ H ₆	34.16	37.30	33.2	29.5
	C ₃ H ₈	28.31	61.15	44.6	37.9
DUT-52	CH ₄	11.85	8.58	16.8	-
	C ₂ H ₆	72.54	56.84	26.7	24.6
	C ₃ H ₈	104.46	97.09	32.8	28.9

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